

	L #	Hits	Search Text
1	L1	27	(reticle or mask) with (chuck\$3 or hold\$3) with (downstream)
2	L2	358	(reticle or mask) with (under) with (chuck\$3 or hold\$3)
3	L3	383	1 or 2
4	L4	134	3 and (355/\$.ccls. or 250/\$.ccls. or 430/\$.ccls.)
5	L5	593257	wafer or substrate
6	L6	110	4 and 5
7	L7	93	3 and (355/\$.ccls. or 250/\$.ccls.)
8	L8	73	7 and 5
9	L9	179	peter.xa. and kim.xa.
10	L10	122392	(wafer or substrate) and (mask or reticle)
11	L11	99	9 and 10
12	L12	1	"5907392".PN.
13	L13	1	"5877845".PN.
14	L14	1	"5798822".PN.

	L #	Hits	Search Text
15	L15	1	"5777722".PN.
16	L16	155	(reticle or mask) with (chuck\$3 or hold\$3) with electrostatic
17	L17	144	16 and 5
18	L18	54	17 and (355/\$.ccls. or 250/\$.ccls.)

AKm
8/16/03